

# Observation of minority fast electron dynamics in a low-pressure RF discharge and magnetic nozzle

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ExB Workshop  
November 2, 2018

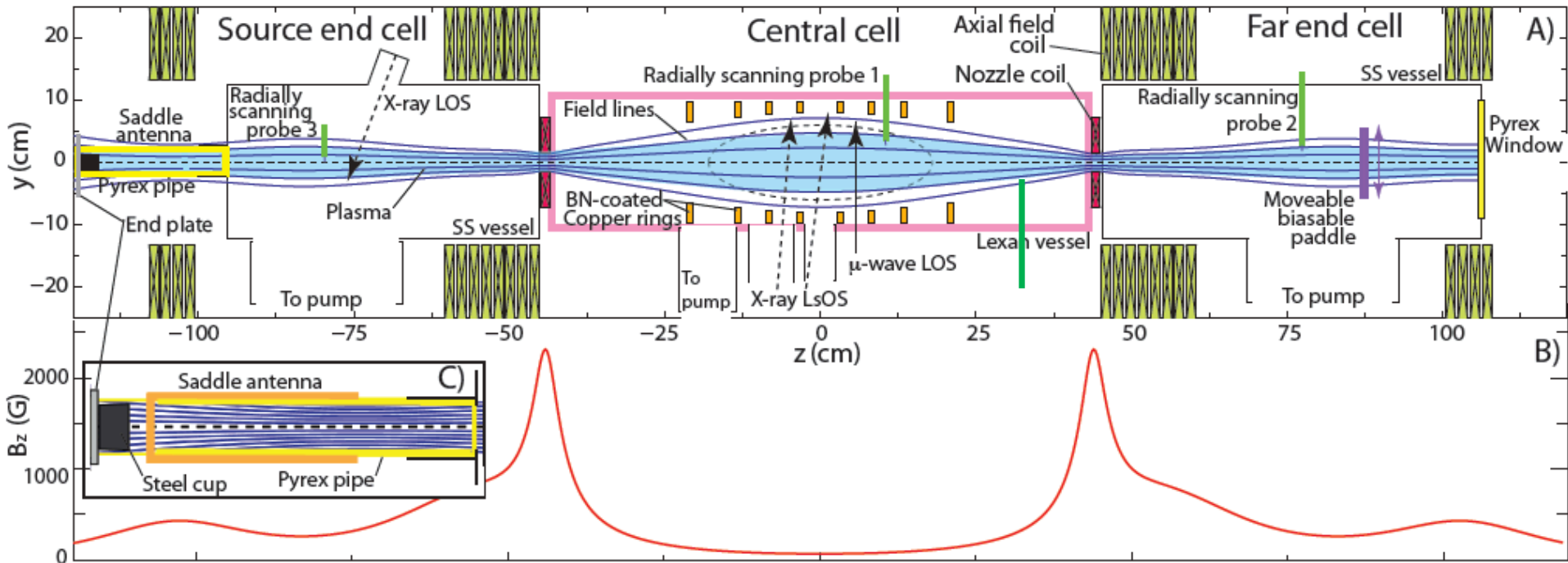
C. Swanson, P. Jandovitz, T. Qian, S. A. Cohen

- PFRC-II run as low-pressure RF-coupled magnetic mirror
- 1% minority electrons: 300 – 600 eV (“warm”) temperature near source
  - Surface interaction: RF self bias and ion-induced secondary electron emission
- 0.1% minority electrons: 1 – 3 keV (“hot”) temperature in mirror
  - Fermi acceleration caused by the 1% warm electrons
- Observed to change **potential structures, power balance, and discharge properties**

# APPARATUS

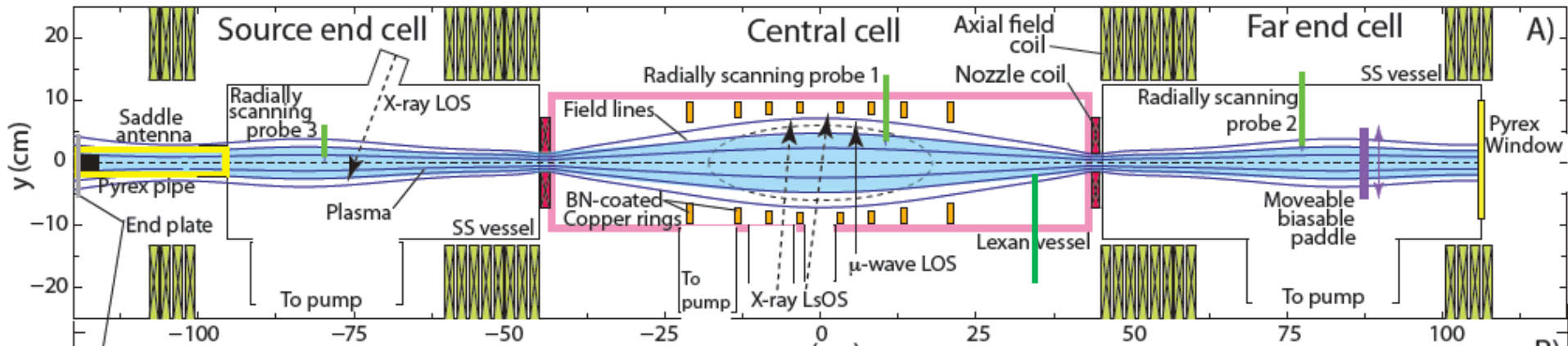
## Apparatus

- 1m central mirror cell
- $B_{\min} \approx 200$  G
- Mirror ratio  $R \approx 10 - 40$
- Pressure 0.01 – 10 mTorr
- 3 cells: Source, Central, Far
- 0 - 500 W at 7 - 27 MHz
- Bulk plasma at  $T_e \approx 5$  eV,  $n_e \approx 10^{10-11} / \text{cm}^3$
- Probes for 0 – 50 eV
- X-ray for 200 eV – 30 keV



The same chambers as the Princeton Field Reversed Configuration Experiment (PFRC)

# MEASUREMENTS



## SEC:

- “Warm” electrons:
  - $T_e \sim 300$  eV
  - $n_e \sim 3 \times 10^8 / \text{cm}^3$
  - 30 W
- RF self-bias

## CC:

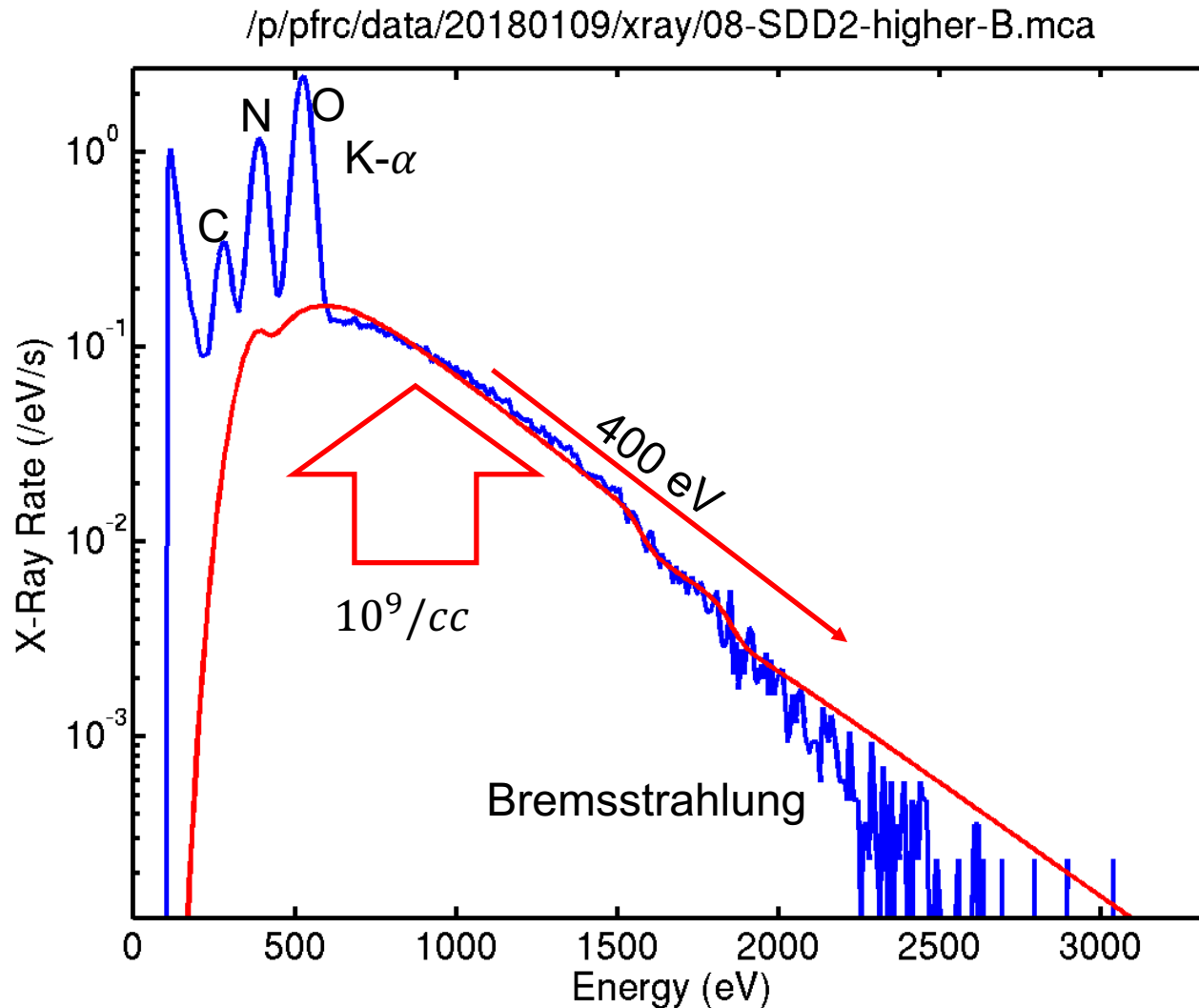
- Warm electrons persist:
  - >300 transits
- “Hot” electrons:
  - $T_e \sim 3$  keV
  - $n_e \sim 3 \times 10^7 / \text{cm}^3$
  - 3 W
  - Individual electrons above 30 keV
  - >10,000 transits
- Potential fluctuation:
  - $\sim 50$  V amplitude
  - $\sim 200$  MHz frequency

## FEC:

- Potential drop:
  - $-600$  V
- Infer beam
- Sputter of tantalum by hydrogen
- Pressure-dependent heat flux

# SEC X-RAY SPECTRUM

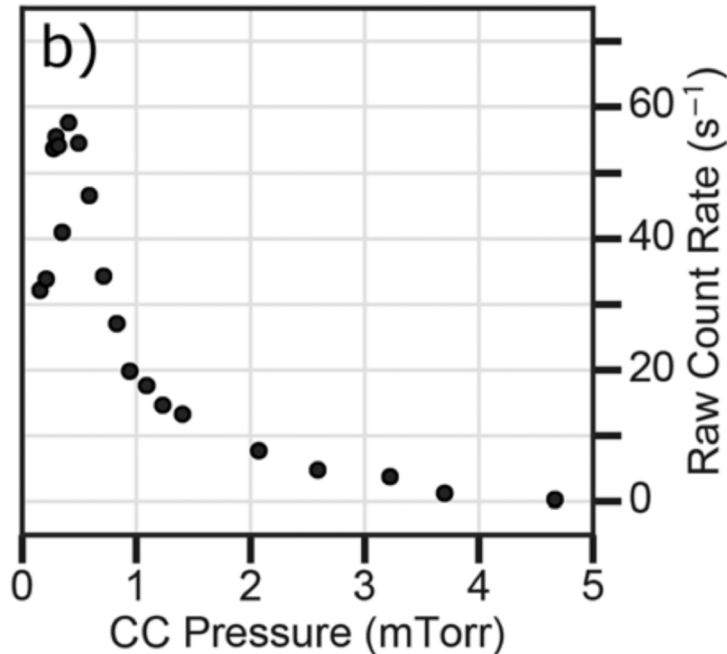
SDD detects  $n_e \approx 10^9/cc$ ,  $T_e \approx 400 eV$  electrons, 1% amongst the bulk population[3][4]



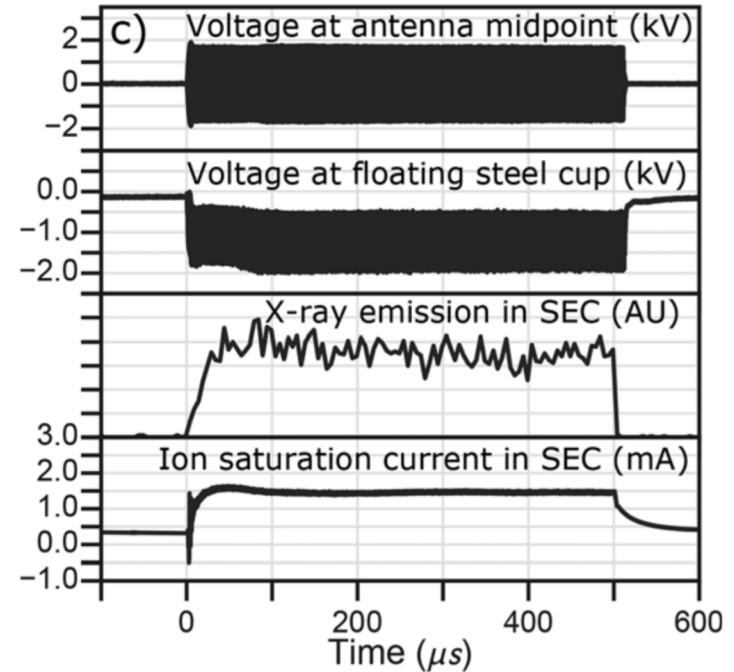
SDD covers energy range of K- $\alpha$  spectral lines from C, N, O, and Bremsstrahlung. Temperature and density are determined from Bremsstrahlung.

# SEC MEASUREMENTS

We deduce: self-bias effect causes very negative potentials on electrode  
Ion-induced secondary electron emission causes electrons to be born and accelerated



X-ray count rate from H<sub>2</sub> plasma vs gas pressure in the SEC. From [3]



Profiles in time: antenna voltage, steel cup voltage, x-ray count rate, Langmuir ion saturation current. From [3]

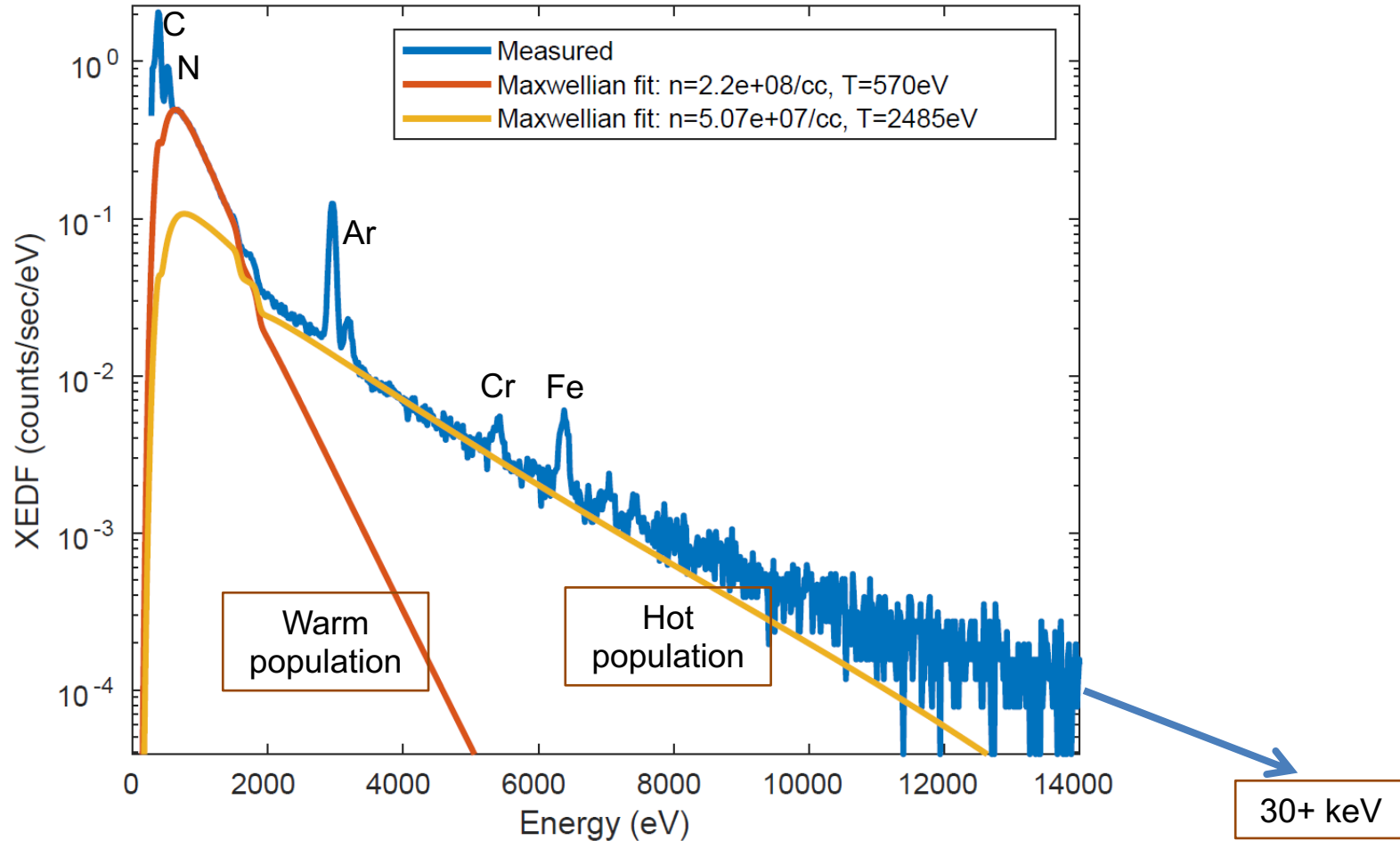
This process is more likely to happen:

When discharge is more **capacitive** than **inductive**.

When **pressure is low** so electron mean free path is long.

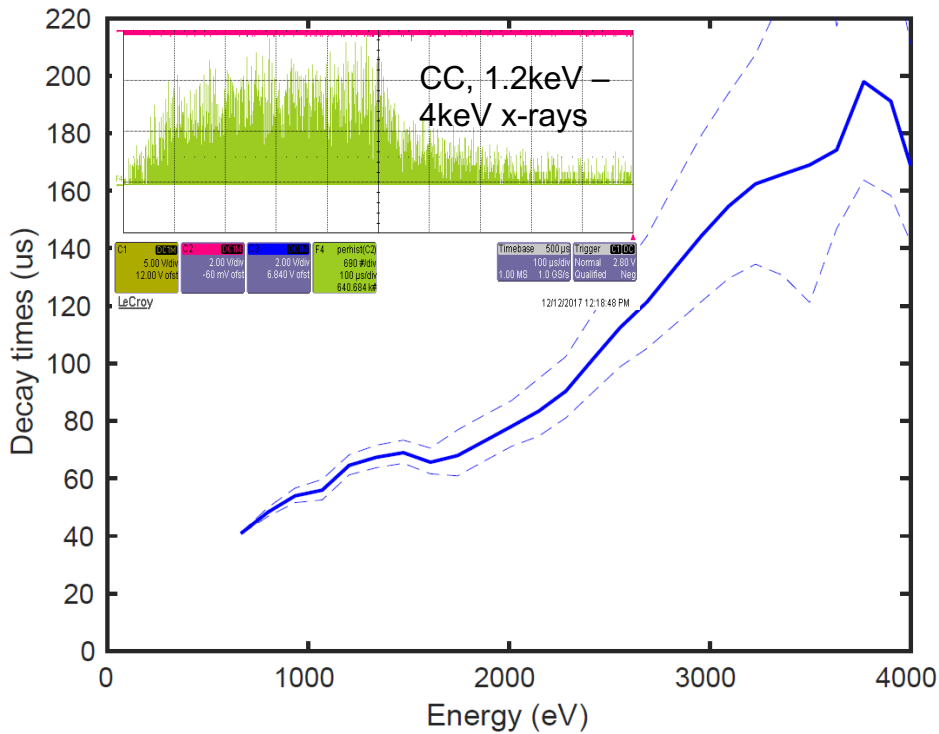
# CC X-RAY SPECTRUM

SDD detects  $n_e \approx 10^8/cc, T_e \approx 3 keV$  electrons, 0.1% amongst the bulk population [4]



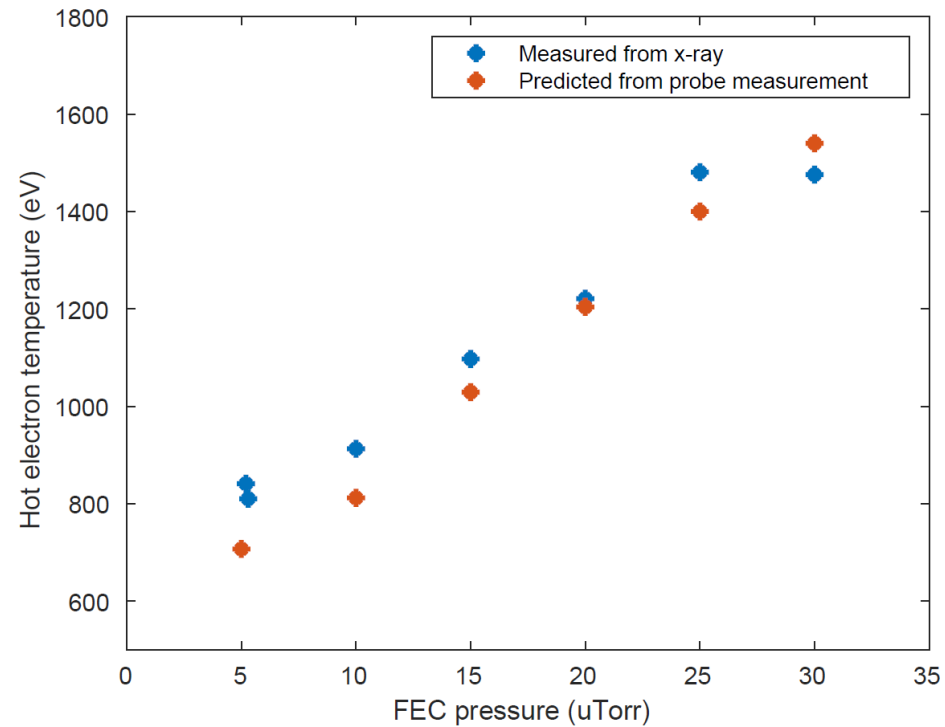
This is quite hot

# CC FLUCTUATION AND X-RAY PROPERTIES



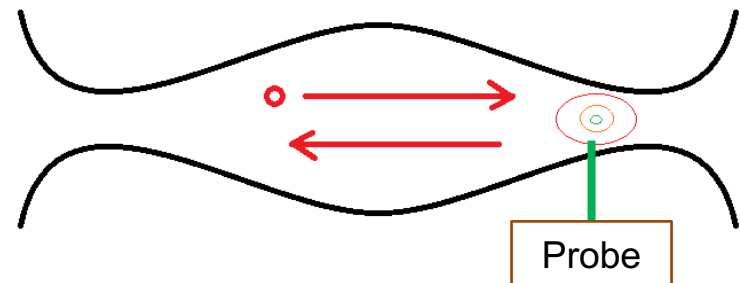
Electrons of higher energy persist for longer time after RF cessation. These are tens of thousands of mirror transits, hundreds of microseconds

$$T_{eff} = \Delta E \sqrt{\frac{\tau}{t_t}}$$



Increasing the FEC pressure:

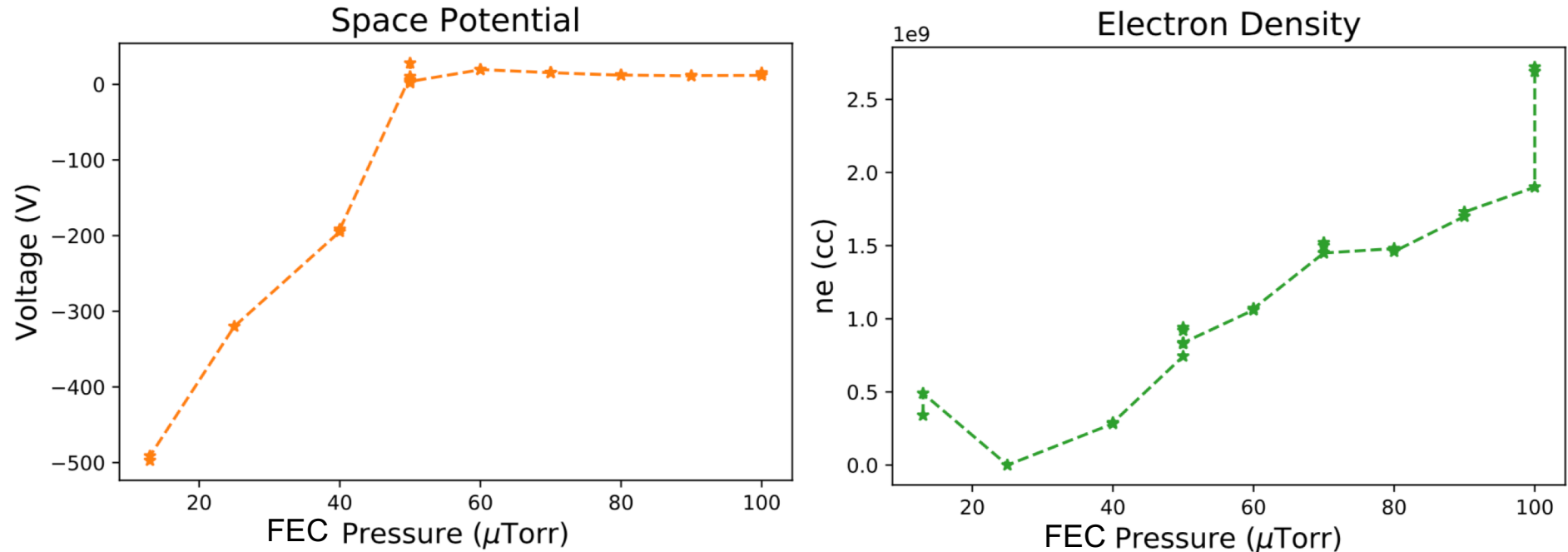
1. Increases the amplitude of the ~200 MHz fluctuation (~50 V)
2. Increases the hot electron temperature proportionally.





# FEC CONDITIONS

Far End Cell (FEC, termination of plasma column) has a Langmuir probe and a Tantalum (low-sputtering) paddle whose floating potential can be measured.[4]



Plots and measurements by Tony Qian for SULI internship

- Space potential is measured to be  $< -600$  V
- Electron density is measured to increase with increasing FEC pressure (ionization)
- We suppose these ionization-born electrons are responsible for the fluctuation in the CC

# FEC PADDLE BEHAVIOR

Far End Cell (FEC, termination of plasma column) has a Langmuir probe and a Tantalum (low-sputtering) paddle whose floating potential can be measured.[4]

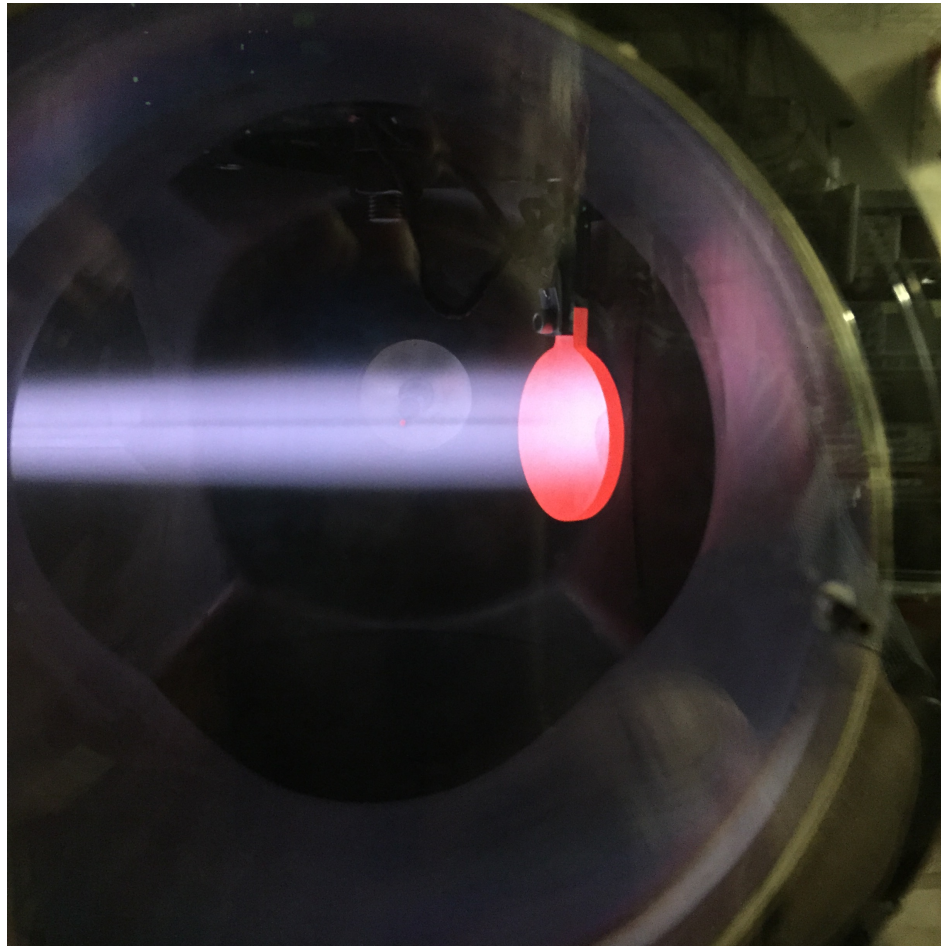


Photo by S. A. Cohen

- Paddle floating potential is measured to be  $< -1$  kV
- Tantalum sputter-coats the FEC regularly (feed gas is Hydrogen)
- Paddle glow is observed under specific circumstances (wait 2 slides)

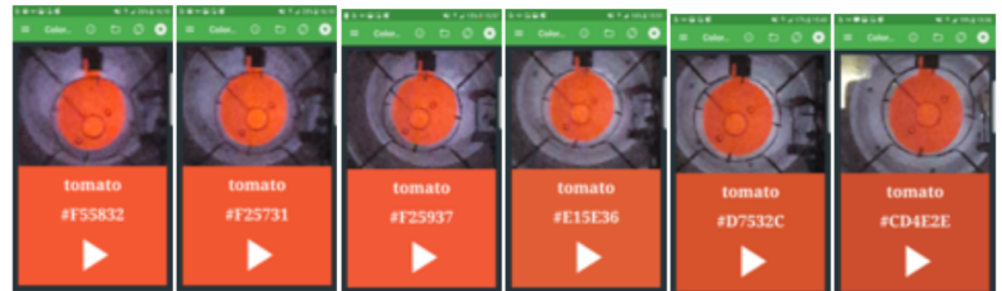
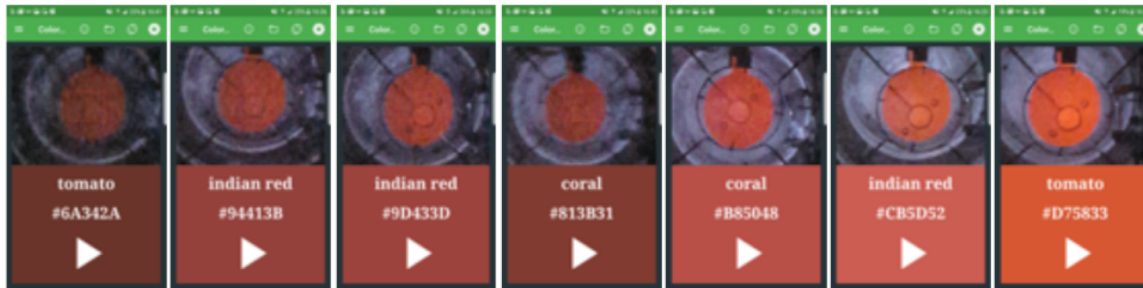
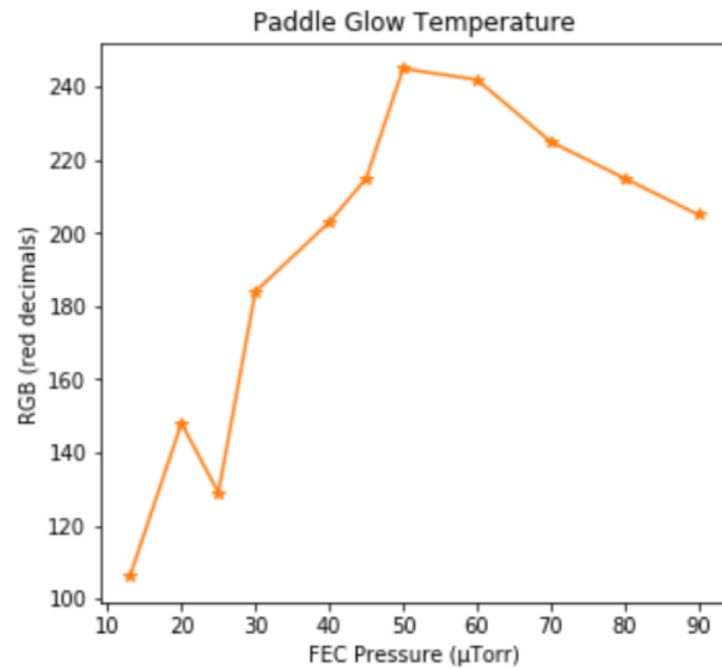
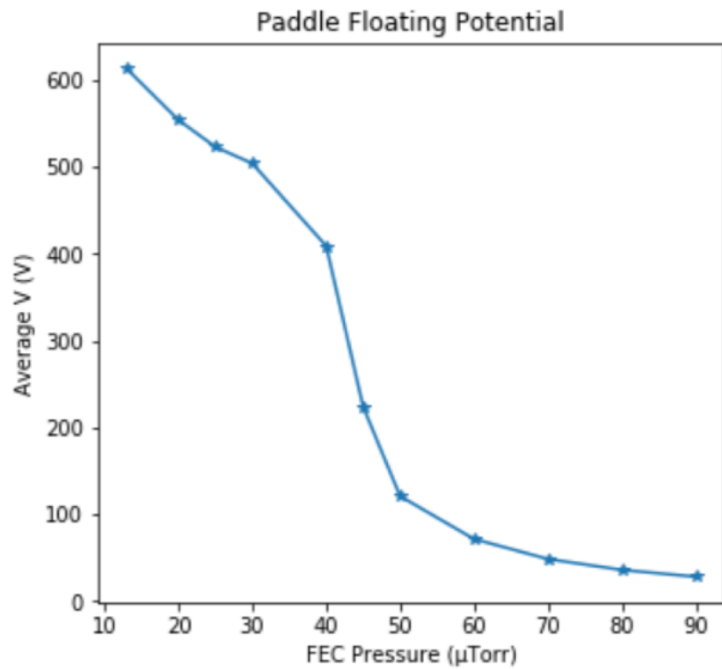
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Photos by S. A. Cohen

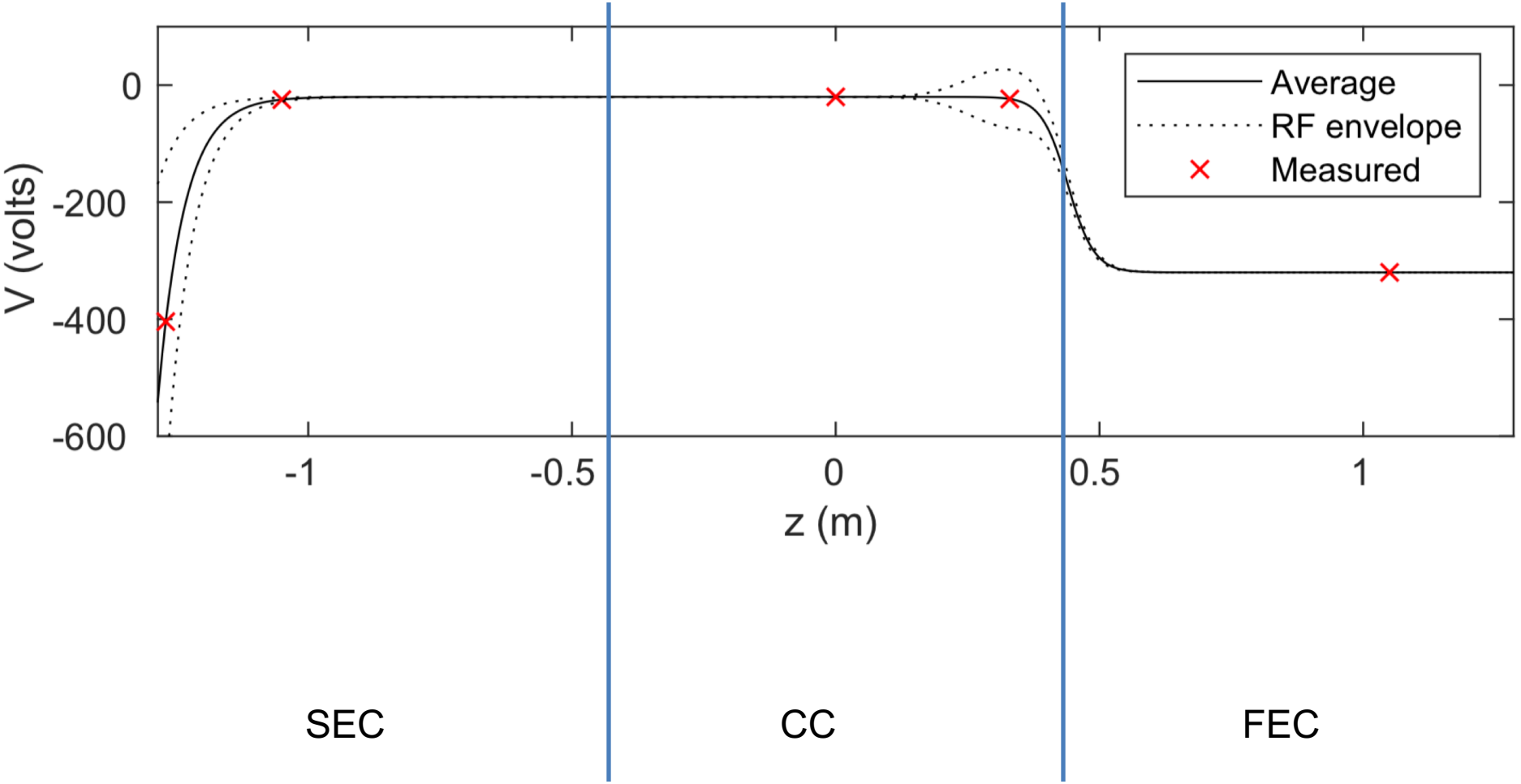
- When plasma is terminated on a sapphire plate: Visibly hollow light emission profile



Reproduced from Tony Qian's presentation to the PFRC group, April 27, 2018

feb 22 data

# SUMMARY: GLOBAL POTENTIAL PROFILE



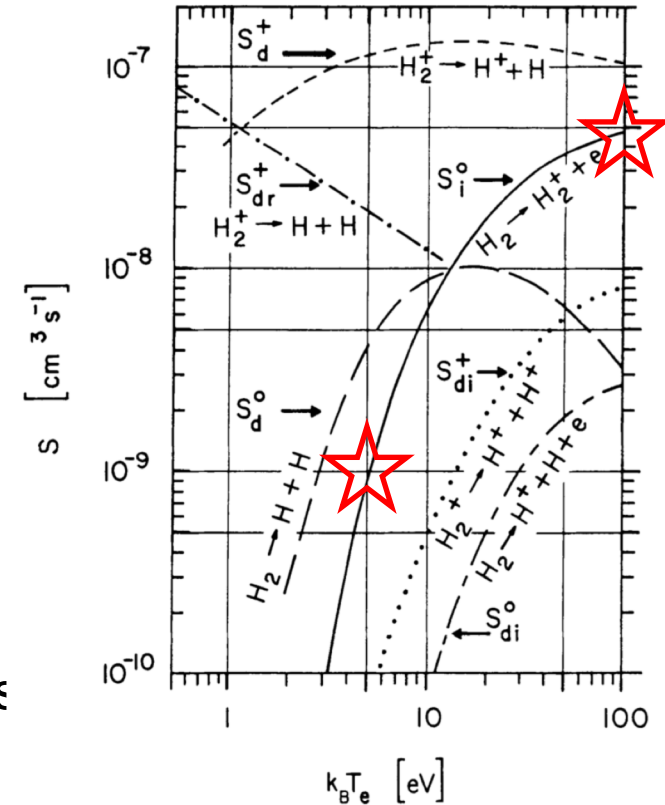
# CONCLUSION

“Might I have fast electrons in my device?”

- Maybe, if you haven't looked for them (x-rays, etc)

“When are fast electrons important?”

- If  $n_f \sqrt{T_f} \sim n_b \sqrt{T_b}$ : Fast particle flux is significant.
  - Potential structures at the nozzles and sheaths
- If  $n_f T_f / \tau_f \sim n_b T_b / \tau_b$ : Power from fast electrons is significant
  - Power balance
- If  $n_f \langle \sigma v \rangle_f \sim n_b \langle \sigma v \rangle_b$ : Ionization from fast electrons is significant
  - Discharge sustained by different process
  - Plasma where you don't expect it



Rate constants, including for ionization, for thermal electrons in Hydrogen. Fast electrons ionize  $\text{H}_2$  >50x more easily. [5]

## REFERENCES

- [1] <http://amptek.com/>
- [2] Swanson, C., P. Jandovitz, and S. A. Cohen. “Using Poisson-Regularized Inversion of Bremsstrahlung Emission to Extract Full Electron Energy Distribution Functions from x-Ray Pulse-Height Detector Data.” *AIP Advances* 8, no. 2 (February 1, 2018): 025222. <https://doi.org/10.1063/1.5019572>.
- [3] Jandovitz, P., C. Swanson, J. Matteucci, R. Oliver, J. Pearcy, and S. A. Cohen. “Demonstration of Fast-Electron Populations in a Low-Pressure, Low-Power, Magnetized RF Plasma Source.” *Physics of Plasmas* 25, no. 3 (March 1, 2018): 030702. <https://doi.org/10.1063/1.4998735>.
- [4] Swanson, C. “Measurement and Characterization of Fast Electron Creation, Trapping, and Acceleration in an RF-Coupled, High-Mirror-Ratio Magnetic Mirror.” Doctoral thesis, Princeton University, 2018.
- [5] Harrison, M. F. A. “Atomic and Molecular Collisions in the Plasma Boundary.” In *Physics of Plasma-Wall Interactions in Controlled Fusion*, edited by D. E. Post and R. Behrisch, 281–349. Boston, MA: Springer US, 1986. [https://doi.org/10.1007/978-1-4757-0067-1\\_7](https://doi.org/10.1007/978-1-4757-0067-1_7).